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### Final Program

The seminar will take place in the lecture hall at  
 PTB, Hermann-von-Helmholtz building, Abbestr 2-12, 10587 Berlin.  
 ready to print: [final\\_program\\_day1.pdf](#) [final\\_program\\_day2.pdf](#)



#### Thursday, October 19

09:00		<b>Registration &amp; Poster Set-up &amp; Coffee</b>	
<b>10:00</b>		<b>Opening</b>	
10:10	M. Richter	<b>VUV and EUV Metrology Activities at PTB</b>	PTB
<b>10:30</b>		<b>Session I: Detectors</b>	
10:30	N. Papanthasiou	<a href="#">SiC-based radiometers: Status, Applications, Outlook</a>	Sglux
10:50	T. Tanaka	<a href="#">Radiometers for free-electron lasers</a>	NMIJ / AIST
11:10	R. Ivanov	<a href="#">Single-shot temporal characterization of soft X-ray SASE FEL</a>	DESY
11:30	O. Pronin	<a href="#">130 W, 240 MW, 30 fs laser oscillator for XUV generation</a>	MPI-QO
11:50		<b>Group Photo</b>	
12:00		<b>Lunch Buffet</b>	
13:00		<b>Poster &amp; Coffee</b>	
<b>14:00</b>		<b>Session II: Instruments</b>	
14:00	J. Larruquert	<a href="#">New tools for optical constant calculation and analysis</a>	IO-CSIC
14:20	P. Zuppella	<a href="#">EUV ellipsometric measurements: a proof of concept</a>	IFN-CNR
14:40	L. Gavilan	<a href="#">XUV optical constants of tholins for the study of Titan's atmosphere</a>	LATMOS
15:00	J.-P. Halain	<a href="#">The Solar Orbiter EUV instrument on-ground calibration activities</a>	CSL
15:20	M. Müller	<a href="#">Soft x-ray spectroscopy and microscopy using a table-top laser-induced plasma source</a>	LLG
15:40	K. Moshhammer	<a href="#">VUV-Radiation for Combustion Chemistry Analysis</a>	PTB
16:00		<b>Coffee</b>	
<b>16:40</b>		<b>Session III: Optics</b>	
16:40	M. Störmer	<a href="#">Ru/C multilayers for X-ray tomography and imaging</a>	HZG
17:00	S. Kroker	<a href="#">Wire grid polarizers for the DUV und VUV spectral range</a>	PTB & TU BS
17:20		<b>End of Sessions</b>	
19:00		<b>Get Together &amp; Dinner Buffet</b>	
22:00		<b>End of Day 1</b>	

#### Friday, October 20<sup>th</sup>

<b>09:00</b>		<b>Session IV: EUVL (I)</b>	
09:00	V. Banine	<a href="#">EUV Lithography now</a>	ASML
09:20	H. Enkisch	<a href="#">Manufacturing and Industrialization of EUV Lithography Optics</a>	CZ SMT
09:40	P. Pennartz	<a href="#">Specific Multilayer Applications in EUV Lithography machines</a>	Rigaku
10:00		<b>Coffee</b>	
<b>10:40</b>		<b>Session V: EUVL (II)</b>	
10:40	N. Chkhalo	<a href="#">Be-based multilayers for EUV spectral range</a>	IPM RAS
11:00	N. Böwering	<a href="#">Cleaning of tin-drop contaminated EUV optics by initiation of phase transformation</a>	U Bielefeld
11:20	T. Feigl	<a href="#">Reflective EUV diffusors</a>	optiFab
11:40	M. Mebonia	<a href="#">Experimental studies of the propagation of programmed buried defects into multilayer coatings</a>	FZ Jülich
12:00		<b>Lunch Buffet</b>	
13:00		<b>Poster &amp; Coffee</b>	
<b>14:00</b>		<b>Session VI: EUV Scattering</b>	
14:00	I. Englard	<a href="#">Multi-dimensional metrology process control challenges for the 5nm node and below</a>	AMIL

14:20	Y. Ekinçi	<a href="#">EUV actinic mask inspection using coherent scattering methods</a>	PSI
14:40	A. Fernandez Herrero	<a href="#">Impact of grating line roughness in the resonant diffuse scattering</a>	PTB
15:00		<b>Wrap-up and Closing</b>	PTB
15:15		<b>End of the Seminar</b>	

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